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Thin Solid Films 269 (1995) 121

thin solid films

Author Index of Volume 269

Ahuja, R., 29
Ashour, A., 112, 117

Baik, H.-K., 102
Banerjee, R., 29
Bates, J.B., 6
Bliznyuk, V.N., 90

Cantalini, C., 97
Carlsson, P., 14
Chen, J.-X., 18
Chen, X.-Y., 18
Chen, Y.-F., 18
Chi, E.-J., 102
Cockeram, B., 57

Du, Y., 47

El-Kadry, N., 112, 117
Eriksson, S., 14
Erokhin, V., 85

Facci, P., 85
Faccio, M., 97
Fraser, H.L., 29

Gruszecki, T., 14
Gutiérrez, M.T., 80

Hampden-Smith, M.J., 51
Hanajiri, T., 41
Herrero, J., 80
Holmström, B., 14
Hsu, D.S.Y., 21

Isobe, S., 36

Jain, A., 51

Katoda, T., 41
Kim, H.-G., 75
Kim, Y.-M., 75
Kirilyuk, A.P., 90
Kodas, T.T., 51
Kwak, B.S., 6
Kwak, J.-S., 102

Lee, S.-M., 102
Lee, W.-J., 75
Liao, K.-J., 108
Liu, B.X., 47
Liu, Z.-G., 18

Machorro, R., 1
Mahmoud, S.A., 112, 117
Martínez, M.A., 80
Matsumoto, Y., 41
Miaoulis, I.N., 64
Ming, N.-B., 18
Miyake, K., 36

Nakaaki, I., 69
Nakamura, S., 69
Nicolini, C., 85

Pan, F., 47
Pelino, M., 97
Pierson, K.W., 21

Radicchi, G., 85
Rosenberg, S.E., 64

Saito, N., 69
Sasase, M., 36
Shim, J.-Y., 102
Siqueiros, J.M., 1
Sugano, T., 41
Sun, H.-T., 97
Sun, L., 18
Swaminathan, S., 29

Takano, I., 36
Tao, K., 47
Troilo, L.M., 21
Turner, N.H., 21
Tuyen, Le.T.T., 41

Wang, G., 57
Wang, S., 1
Wang, W.-L., 108
Wong, P.Y., 64

Yamaguchi, T., 69
Yoshioka, S., 69
Yu, T., 18

Zhang, Z.-G., 108
Zhu, Y.-Y., 18
Zuhr, R.A., 6

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ELSEVIER

Thin Solid Films 269 (1995) 122–124

thin solid films

Subject Index of Volume 269

Aluminium
resistivity of titanium–aluminum multilayered thin films, 29
Aluminium nitride
interface reactions of an Ag/Cr/AlN sandwich during annealing between 250 and 650 °C, 47
Amorphization
formation of amorphous and crystalline phases, and phase transition by solid-state reaction in Zr/Si multilayer thin films, 102
Annealing
interface reactions of an Ag/Cr/AlN sandwich during annealing between 250 and 650 °C, 47

Cadmium selenide
electrochemically deposited polycrystalline n-CdSe thin films studied with laterally resolved photoelectrochemistry and SEM, 14
Cadmium sulphide
on the electrical and optical properties of CdS films thermally deposited by a modified source, 117
Cadmium telluride
structural dependence of d.c. electrical properties of physically deposited CdTe thin films, 112
Capacitors
structural dependence of d.c. electrical properties of physically deposited CdTe thin films, 112
Catalysis
photocurrent performance of TiO_x films prepared by Ar^+ ion beam-assisted reactive deposition method, 36
Chemical vapour deposition
preparation and characterization of $PbTiO_3$ thin films by metalorganic chemical vapor deposition on a $La_{0.5}Sr_{0.5}CoO_3$ metallic oxide electrode, 18
selective area platinum silicide film deposition using a molecular precursor chemical beam source, 21
cathodoluminescence and positron annihilation of defects in diamond films formed by d.c. plasma CVD, 108
Chromium
interface reactions of an Ag/Cr/AlN sandwich during annealing between 250 and 650 °C, 47
Conductivity
influence of deposition conditions on the properties of a-GeC:H and a-Ge:H films prepared by r.f. magnetron sputtering, 69
Copper
thermal dry-etching of copper using hydrogen peroxide and hexafluoroacetylacetone, 51
Crystallization
formation of amorphous and crystalline phases, and phase transition by solid-state reaction in Zr/Si multilayer thin films, 102

Deposition process
deposition of organic–inorganic composite thin films by Li_3PO_4 sputtering and C_2H_4 plasma polymerization, 6
electrochemically deposited polycrystalline n-CdSe thin films studied with laterally resolved photoelectrochemistry and SEM, 14
on the electrical and optical properties of CdS films thermally deposited by a modified source, 117
Diamond
cathodoluminescence and positron annihilation of defects in diamond films formed by d.c. plasma CVD, 108
Dielectrics
Pt-base electrodes and effects on phase formations and electrical properties of high-dielectric thin films, 75
Diffusion
the influence of multi-layered kinetics on the selection of the primary phase during the diffusion-controlled growth of titanium-silicide layers, 57

Electrical properties and measurements
electrical and optical properties of phosphorous nitride films formed on InP substrates with photon-assisted chemical vapour deposition, 41
Pt-base electrodes and effects on phase formations and electrical properties of high-dielectric thin films, 75
structural dependence of d.c. electrical properties of physically deposited CdTe thin films, 112
Electrochemistry
electrochemically deposited polycrystalline n-CdSe thin films studied with laterally resolved photoelectrochemistry and SEM, 14
Ellipsometry
optical properties of Mg, from UV to IR, using ellipsometry and reflectometry, 1
Etching
thermal dry-etching of copper using hydrogen peroxide and hexafluoroacetylacetone, 51
Ethylene
deposition of organic–inorganic composite thin films by Li_3PO_4 sputtering and C_2H_4 plasma polymerization, 6
Evaporation
structural dependence of d.c. electrical properties of physically deposited CdTe thin films, 112

Fluorescence
on the mobility of Immunoglobulines G in Langmuir–Blodgett films, 85

Germanium
a theoretical study of the effect of thermal annealing on curvature changes in multilayered structures, 64
influence of deposition conditions on the properties of a-GeC:H and a-Ge:H films prepared by r.f. magnetron sputtering, 69

Elsevier Science S.A.

Growth mechanism
the influence of multi-layered kinetics on the selection of the primary phase during the diffusion-controlled growth of titanium-silicide layers, 57

Heat treatment
a theoretical study of the effect of thermal annealing on curvature changes in multilayered structures, 64
Heterostructures
preparation and characterization of $PbTiO_3$ thin films by metalorganic chemical vapor deposition on a $La_{0.5}Sr_{0.5}CoO_3$ metallic oxide electrode, 18

Indium oxide
optimisation of indium tin oxide thin films for photovoltaic applications, 80
Indium phosphide
electrical and optical properties of phosphorous nitride films formed on InP substrates with photon-assisted chemical vapour deposition, 41
Interfaces
interface reactions of an Ag/Cr/AlN sandwich during annealing between 250 and 650 °C, 47
Ion bombardment
photocurrent performance of TiO_x films prepared by Ar^+ ion beam-assisted reactive deposition method, 36
Iron oxide
NO_2 gas sensitivity of sol–gel-derived α-Fe_2O_3 thin films, 97

Langmuir–Blodgett films
on the mobility of Immunoglobulines G in Langmuir–Blodgett films, 85
highly asymmetric differential X-ray reflectometry of multilayer films, 90
Luminescence
cathodoluminescence and positron annihilation of defects in diamond films formed by d.c. plasma CVD, 108

Magnesium
optical properties of Mg, from UV to IR, using ellipsometry and reflectometry, 1
Metallization
thermal dry-etching of copper using hydrogen peroxide and hexafluoroacetylacetone, 51
Multilayers
resistivity of titanium–aluminum multilayered thin films, 29
the influence of multi-layered kinetics on the selection of the primary phase during the diffusion-controlled growth of titanium-silicide layers, 57
on the mobility of Immunoglobulines G in Langmuir–Blodgett films, 85
highly asymmetric differential X-ray reflectometry of multilayer films, 90

Nitrides
electrical and optical properties of phosphorous nitride films formed on InP substrates with photon-assisted chemical vapour deposition, 41
Nitrogen dioxide
NO_2 gas sensitivity of sol–gel-derived α-Fe_2O_3 thin films, 97
Nucleation
selective area platinum silicide film deposition using a molecular precursor chemical beam source, 21

Optical properties
optical properties of Mg, from UV to IR, using ellipsometry and reflectometry, 1
electrical and optical properties of phosphorous nitride films formed on InP substrates with photon-assisted chemical vapour deposition, 41
influence of deposition conditions on the properties of a-GeC:H and a-Ge:H films prepared by r.f. magnetron sputtering, 69
on the electrical and optical properties of CdS films thermally deposited by a modified source, 117
Optical spectroscopy
optical properties of Mg, from UV to IR, using ellipsometry and reflectometry, 1
Oxidation
thermal dry-etching of copper using hydrogen peroxide and hexafluoroacetylacetone, 51
Oxides
preparation and characterization of $PbTiO_3$ thin films by metalorganic chemical vapor deposition on a $La_{0.5}Sr_{0.5}CoO_3$ metallic oxide electrode, 18

Phase transitions
formation of amorphous and crystalline phases, and phase transition by solid-state reaction in Zr/Si multilayer thin films, 102
Photoconductivity
photocurrent performance of TiO_x films prepared by Ar^+ ion beam-assisted reactive deposition method, 36
Piezoelectric effect
preparation and characterization of $PbTiO_3$ thin films by metalorganic chemical vapor deposition on a $La_{0.5}Sr_{0.5}CoO_3$ metallic oxide electrode, 18
Platinum
selective area platinum silicide film deposition using a molecular precursor chemical beam source, 21
Pt-base electrodes and effects on phase formations and electrical properties of high-dielectric thin films, 75
Polymers
deposition of organic–inorganic composite thin films by Li_3PO_4 sputtering and C_2H_4 plasma polymerization, 6
Positron spectroscopy
cathodoluminescence and positron annihilation of defects in diamond films formed by d.c. plasma CVD, 108

Resistivity
resistivity of titanium–aluminum multilayered thin films, 29
on the electrical and optical properties of CdS films thermally deposited by a modified source, 117

Scanning electron microscopy
electrochemically deposited polycrystalline n-CdSe thin films studied with laterally resolved photoelectrochemistry and SEM, 14
Semiconductors
optimisation of indium tin oxide thin films for photovoltaic applications, 80
Sensors
NO_2 gas sensitivity of sol–gel-derived α-Fe_2O_3 thin films, 97
Silicides
selective area platinum silicide film deposition using a molecular precursor chemical beam source, 21
formation of amorphous and crystalline phases, and phase transition by solid-state reaction in Zr/Si multilayer thin films, 102

Silicon
a theoretical study of the effect of thermal annealing on curvature changes in multilayered structures, 64
Silver
interface reactions of an Ag/Cr/AlN sandwich during annealing between 250 and 650 °C, 47
Solar cells
optimisation of indium tin oxide thin films for photovoltaic applications, 80
Sputtering
deposition of organic–inorganic composite thin films by Li_3PO_4 sputtering and C_2H_4 plasma polymerization, 6
influence of deposition conditions on the properties of a-GeC:H and a-Ge:H films prepared by r.f. magnetron sputtering, 69
optimisation of indium tin oxide thin films for photovoltaic applications, 80
Stress
a theoretical study of the effect of thermal annealing on curvature changes in multilayered structures, 64
Titanium
resistivity of titanium–aluminum multilayered thin films, 29
Titanium oxide
photocurrent performance of TiO_x films prepared by Ar^+ ion beam-assisted reactive deposition method, 36
Titanium silicide
the influence of multi-layered kinetics on the selection of the primary phase during the diffusion-controlled growth of titanium-silicide layers, 57

X-ray diffraction
highly asymmetric differential X-ray reflectometry of multilayer films, 90
X-ray total reflection analysis
highly asymmetric differential X-ray reflectometry of multilayer films, 90